Monday, September 15

12:55-16:45 Short Course 1(301, 3rd Floor), Short Course 2 (302, 3rd Floor)
17:00-18:00 Special Talk Session (302, 3rd Floor)
18:00-19:30 Welcome Reception (315, 3rd Floor)

Tuesday, September 16

9:00-11:35 Opening and Plenary Session (301-304)

Lunch

Room A (301, 3rd Floor)	Room B (302, 3rd Floor)	Room C (303, 3rd Floor)	Room D (304, 3rd Floor)	Room E (311, 3rd Floor)	Room F (312, 3rd Floor)	Room G (313, 3rd Floor)	Room H (314, 3rd Floor)	Room J (411+412, 4th Floor)	Room K (413, 4th Floor)	Room M (414+415, 4th Floor)	Room N (416+417, 4th Floor)
13:30-15:15 [A-1] CFET Technology	**13:30-15:00** [B-1] 3D NAND Flash Memory	**13:30-15:00** [C-1] Power and Sensing Circuits	**13:30-15:15** [D-1] Spintronics/Quantum Materials/Reservoir Computing	**13:30-15:00** [E-1] Photovoltaics	**13:30-15:00** [F-1] Organic/Inorganic Hybrid Electronics	**13:30-15:00** [G-1] Integrated Photonics	**13:30-15:00** [H-1] Group IV Materials	**13:30-15:00** [J-1] 3D Integration	**13:30-15:00** [K-1] Growth	**13:30-15:00** [M-1] SiC Materials and Processes	**13:30-15:00** [N-1] Oxide Semiconductor Devices 1
Coffee Break											
15:30-17:00 [A-2] Threshold Voltage Control	**15:30-17:00** [B-2] In-Memory and Unconventional Computing 1	**15:30-16:45** [C-2] Device Circuit Co-Design		**15:30-16:45** [E-2] Thermoelectric Devices and Materials	**15:30-17:00** [F-2] Organic Electronics	**15:30-17:00** [G-2] Light Sources	**15:30-16:45** [H-2] Wide Bandgap and Oxide Materials I	**15:30-17:00** [J-2] Advanced Devices	**15:30-17:00** [K-2] Characterization I	**15:30-17:00** [M-2] THz and High-speed Devices	**15:15-17:00** [N-2] Oxide Semiconductor Devices 2

18:30-20:30 Banquet (Cruise on the Marine Rouge)

Wednesday, September 17

Room A (301, 3rd Floor)	Room B (302, 3rd Floor)	Room C (303, 3rd Floor)	Room D (304, 3rd Floor)	Room E (311, 3rd Floor)	Room F (312, 3rd Floor)	Room G (313, 3rd Floor)	Room H (314, 3rd Floor)	Room J (411+412, 4th Floor)	Room K (413, 4th Floor)	Room M (414+415, 4th Floor)	Room N (416+417, 4th Floor)
9:00-10:30 [A-3] Process Technology and Characterization	**9:00-10:15** [B-3] Ferroelectric Devices				**9:00-10:15** [F-3] Oscillators and Interface Circuits	**9:00-10:15** [G-3] Advanced Photonic Designs	**9:00-10:15** [H-3] Wide Bandgap and Oxide Materials II	**9:45-10:15** [J-3] 3D Integration/Novel Materials	**9:00-10:15** [K-3] Device I	**9:00-10:15** [M-3] Ga203 Power Devices	**9:00-10:15** [N-3] Oxide Semiconductor Devices 3
Coffee Break											
10:45-12:15 [A-4] Cryo CMOS and SOI Technology	**10:45-12:15** [B-4] Ferroelectric Memory Devices			**10:45-12:15** [E-4] ReRAM	**10:45-12:00** [F-4] AI Computing Circuits	**10:45-11:45** [G-4] UV Photonics	**10:45-12:00** [H-4] Characterization and Device Applications	**10:45-12:00** [J-4] 3D Integration/Packaging/Sensors/Novel Materials	**10:45-12:00** [K-4] Characterization II	**10:45-12:00** [M-4] GaN, Ga2O3 Processes	**10:45-12:00** [N-4] Oxide Semiconductor Devices 4
Lunch											
13:30-14:00 [SO-PS-01] Short Oral Presentation	**13:30-14:32** [SO-PS-02] Short Oral Presentation			**13:30-13:42** [SO-PS-06] Short Oral Presentation **14:14-14:28** [SO-PS-09] Short Oral Presentation	**13:30-13:56** [SO-PS-07] Short Oral Presentation **14:15-14:35** [SO-PS-12] Short Oral Presentation	**13:30-14:10** [SO-PS-05] Short Oral Presentation	**14:00-14:28** [SO-PS-11] Short Oral Presentation	**14:15-14:31** [SO-PS-03] Short Oral Presentation	**13:30-14:12** [SO-PS-08] Short Oral Presentation	**13:30-14:20** [SO-PS-04] Short Oral Presentation	**13:30-14:10** [SO-PS-10] Short Oral Presentation
Coffee Break											

15:00-17:00 Poster Session (Conference room 303+304)

Thursday, September 18

Room A (301, 3rd Floor)	Room B (302, 3rd Floor)	Room C (303, 3rd Floor)	Room D (304, 3rd Floor)	Room E (311, 3rd Floor)	Room F (312, 3rd Floor)	Room G (313, 3rd Floor)	Room H (314, 3rd Floor)	Room J (411+412, 4th Floor)	Room K (413, 4th Floor)	Room M (414+415, 4th Floor)	Room N (416+417, 4th Floor)
9:00-10:30 [A-5] CFET Technology and Self-heating	**9:00-10:15** [B-5] Ferroelectric FET			**9:00-10:30** [E-5] Qubit Technology	**9:00-10:15** [F-5] Highly Sensitive Devices for Chem/Bio Detection 1	**9:00-10:00** [G-5] Photonic Computing	**9:00-10:15** [H-5] Low Dimensional Materials I	**9:00-10:15** [J-5] In-Memory and Unconventional Computing 2	**9:00-10:15** [K-5] Device II	**9:00-10:15** [M-5] Emerging Materials and Devices	**09:00-10:00** [N-5] Ferroelectric Memories and Gate Stack
Coffee Break											
10:45-12:00 [A-6] Integration Technology on Si Wafer	**10:45-12:15** [B-6] Emerging Memory Devices, and DRAM			**10:45-12:00** [E-6] Qubit Systems	**10:45-12:00** [F-6] Highly Sensitive Devices for Chem/Bio Detection 2	**10:45-11:45** [G-6] Materials for Photodetector	**10:45-11:45** [H-6] Low Dimensional Materials II	**10:45-12:15** [J-6] Emerging Memory Devices, and DRAM	**10:45-11:45** [K-6] Characterization III	**10:45-12:00** [M-6] III-V High-frequency and Power Devices	**10:15-12:15** [N-6] Group-IV, III-V based Thin-film Growth, and Device Application
Lunch											
13:30-14:45 [A-7] 2D Material Integration	**13:30-14:45** [B-7] Ferroelectric Materials			**13:30-14:45** [E-7] Energy Related Materials	**13:30-14:45** [F-7] Bio/Medical Electronics		**13:30-14:45** [H-7] Advanced Materials and Thin Films		**13:30-14:30** [K-7] Device III	**13:30-14:45** [M-7] Technologies for GaN HEMTs	
Coffee Break											
15:15-16:15 [A-8] Vertical FET and New Devices	**15:15-16:30** [B-8] Ferroelectric Memory Materials								**15:15-16:00** [K-8] Device IV	**15:15-16:30** [M-8] Si Materials and Devices	

Area Scope

- Area 1: Advanced CMOS: Material Science / Process Engineering / Device Technology
- Area 2: Advanced and Emerging Memories / New Applications
- Area 3: Heterogeneous and 3D Integration / Interconnect / MEMS
- Area 4: Power / High-speed Devices and Materials
- Area 5: Photonics: Devices / Integration / Related Technology
- Area 6: Energy Harvesting and Converting Devices and Materials

Area Scope

- Area 7: Organic / Molecular / Bio--electronics
- Area 8: Low Dimensional Devices and Materials
- Area 9: Novel Functional / Quantum / Spintronic Devices and Materials
- Area 10: Thin Film Electronics: Oxide / Non--single Crystalline / Novel Process
- Area 11: Advanced Materials: Synthesis / Crystal Growth / Characterization
- Area12: Advanced and Innovative Circuits / Systems Interacting with Devices and Materials